ABSTRACT

Disclosed are a support device, a heater, and a semiconductor process apparatus. The support device disclosed is applied to a heater of a semiconductor process apparatus, to support a heater body of the heater, where the support device disclosed includes a plurality of support units; the plurality of support units are arranged circumferentially, and each support unit includes a plurality of insulating support bodies sequentially stacked; and a first end portion of each insulating support body is provided with a first limiting portion, and a second end portion, oriented away from the first end portion, of the insulating support body is provided with a second limiting portion; and in each support unit, the first limiting portion of one of any two adjacent insulating support bodies and the second limiting portion of the other of the two adjacent insulating support bodies are in limiting engagement in a first axial direction, and each insulating support body is configured for supporting engagement with the heater body, where the first axial direction is parallel to a stacking direction of the plurality of insulating support bodies. The solution can solve the problem that a heater body support device in the related art is likely to cause deformation of a heater body after thermal expansion and contraction deformation.